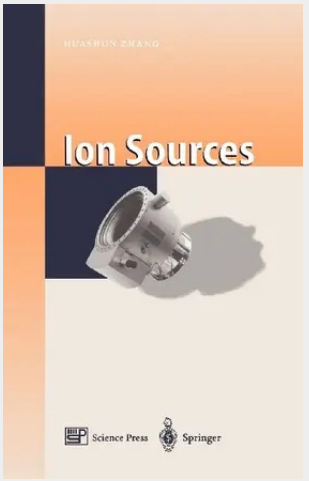
Zhang

Ion Sources

Ion implantation has become a basic technology in device manufacturing. For efficient use of this accelerator-based technique the choice of appropriate ion sources is important. This book deals with the design and operation of ion sources. Additionally the physics of ion formation of the various elements with different charge states and charge neutralization are discussed. Ion selection and beam diagnostics are part of the book too. The presentation of the necessary equations and diagrams for the various parameters makes this book useful as a handbook for ion sources.

This book is the most comprehensive book on ion sources as part of ion implantation technology, a newly established basic technology for microelectronic device processing. It appeals to physicists, engineers and advanced students active in ion implantation and ion beam physics.



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